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APPLICATION NO.	FI	LING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/521,544	C	01/14/2005	Shiro Sakai	08228/071001	9344	
22511	7590	02/28/2006		EXAMINER		
OSHA LIA	NG L.L.F	Ρ.	ABRAHAM, FETSUM			
1221 MCKIN	NEY STI	REET				
SUITE 2800				ART UNIT	PAPER NUMBER	
HOUSTON,	TX 770	10		2826		

DATE MAILED: 02/28/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

			H'!
	Application No.	Applicant(s)	
	10/521,544	SAKAI ET AL.	
Office Action Summary	Examiner	Art Unit	<del> </del>
	Fetsum Abraham	2826	
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the	correspondence address	S
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D  - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATIO 36(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	N. mely filed the mailing date of this commun ED (35 U.S.C. § 133).	·
Status			
Responsive to communication(s) filed on      This action is FINAL. 2b) ☑ This      Since this application is in condition for alloware closed in accordance with the practice under Expression in the practice of	s action is non-final.  nce except for formal matters, pre		its is
Disposition of Claims			
4) Claim(s) 1-11 is/are pending in the application 4a) Of the above claim(s) is/are withdray 5) Claim(s) is/are allowed. 6) Claim(s) the rest is/are rejected. 7) Claim(s) 4-7,9,10 is/are objected to. 8) Claim(s) are subject to restriction and/o Application Papers  9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) accomposition and applicant may not request that any objection to the Replacement drawing sheet(s) including the correct	wn from consideration.  or election requirement.  er.  epted or b) objected to by the drawing(s) be held in abeyance. Se tion is required if the drawing(s) is objected to by the drawing(s).	e 37 CFR 1.85(a). njected to. See 37 CFR 1.1	
11) The oath or declaration is objected to by the Ex	caminer. Note the attached Office	Action or form PTO-15	52.
Priority under 35 U.S.C. § 119  12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicat rity documents have been receive u (PCT Rule 17.2(a)).	ion No ed in this National Stag	e
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  Paper No(s)/Mail Date	4)  Interview Summary Paper No(s)/Mail D 5)  Notice of Informal F 6)  Other:		

Application/Control Number: 10/521,544

Art Unit: 2826

## **DETAILED ACTION**

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1,8 are rejected under 35 U.S.C. 102(b) as being anticipated by McIntosh et al (5,851,905).

The patent discloses a compound semiconductor device in figures 3,4 comprising a multilayered quantum well composed of AllnGaAs barrier layer (11) and an InGaN layer (12) formed on substrate (15).

The following is taught in the patent in regards to the structures:

Detailed Description Text (27):

As already described with respect to FIGS. 1-4 and 6-9, <u>quantum well</u> light emitting diodes according to the invention include <u>quantum well</u> layers having controlled amounts of indium. <u>The percentage of indium may be as high as 90% or more in order to obtain a desired frequency of emission. Unfortunately, heretofore it has been extremely difficult to obtain device quality indium gallium nitride or aluminum indium gallium nitride films using MBE or MOCVD techniques. Also, for high InN%, indium metal droplets can segregate at the interface between the InGaN active layer and the AlGaN or AlInGaN barrier layers. The presence of these In droplets can affect or even dominate the properties of these devices.</u>

emission takes place is an AllnGaN compound layer.

As for claim 8, the barrier layer (11c) adjacent the active layer where light

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 2-3 are rejected under 35 U.S.C. 103(a) as being unpatentable over Mcintosh et al in view of Goetz et al (6,489,636).

The primary reference teaches all subject matter claimed but may have omitted to discuss the claimed In composition in the InGaN layer. It, however, discussed an important issue as the follows:

## <u>Detailed Description Text</u> (27):

As already described with respect to FIGS. 1-4 and 6-9, <u>quantum well</u> light emitting diodes according to the invention include <u>quantum well</u> layers having controlled amounts of indium. The percentage of indium may be as high as 90% or more in order to obtain a desired frequency of emission. Unfortunately, heretofore it has been extremely difficult to obtain device quality indium gallium nitride or aluminum indium gallium nitride films using MBE or MOCVD techniques. Also, for high InN%, indium metal droplets can segregate at the interface between the <u>InGaN</u> active layer and the AlGaN or <u>AlInGaN</u> barrier layers. The presence of these In droplets can affect or even dominate the properties of these devices.

Clearly, the information reveals the role of In composition in such compound oriented layers specifically in relation to frequency of emission.

The primary reference teaches all subject matter claimed with the exception of the claimed In concentration is the claimed compound. The secondary reference, however, discloses a light sensitive material similar to the claimed invention and teaches the following about In concentration in its quantum layers:

## <u>Detailed Description Text</u> (4):

A spacer layer 15 separates active region 16 from smoothing layer 14. Spacer layer 15 typically does not contain In and may be, for example, GaN or AlGaN. Active region 16 is typically a multiple quantum well structure of AlInGaN or InGaN, with an indium composition between 5 and 50% and an aluminum composition between 0 and 50%. A p-type region 17 is formed over the active region. P-contact 19 is formed on the upper surface of p-type region 17, and an n-contact 18 is formed on an exposed portion of n-type region 12. Alternatively, n-contact 18 is formed on an exposed portion of smoothing layer 14, as illustrated in FIG. 2. in figures 3,4 comprising a multilayered quantum well composed of AlInGaAs barrier layer (11) and an InGaN layer (12) formed on substrate (15).

While atomic composition of a compound semiconductor layer may be variable in nature that depends on desired effect of a given compound, the secondary reference, however, meets the claimed In composition in the respective layer. Therefore, it would have been obvious to one skilled in the art to limit In composition in the claimed

dominate overall device optical characteristics.

compound to the claimed range in order to avoid undesired level of In effects to

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Claim 11 is rejected under 35 U.S.C. 103(a) as being unpatentable over McIntosh et al.

As for claim 11, "product by process" claims are directed to the product per se, no matter how actually made, In re Hirao, 190 USPQ 15 at 17 (footnote 3). See also In re Brown, 173 USPQ 685 and In re Thorpe, 227 USPQ 964, 966. Therefore, the way the product was made does not carry any patentable weight as long as the claims are directed to a device. Further, note that the applicant has the burden of proof in such cases, as the above case law makes clear. Also see MPEP 2113.

Claims 4-7,9,10 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims. The claims, of course, are subject to more intense search in the progression of activities ahead of time.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fetsum Abraham whose telephone number is: 571-272-1911. The examiner can normally be reached on 8:00 - 18:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan J Flynn can be reached on 571-272-1915.

Felsun/Abraham 2/14/06